

CLAIMS LISTING

- 1.(currently amended) A method for coating a phosphor or a scintillator layer onto a flexible substrate, within a sealed zone maintained under vacuum conditions, by the step of vapor deposition, wherein said phosphor or scintillator layer is deposited onto said substrate in successive steps, characterized in that said substrate is deformed at least before, during or after said step of vapor deposition.
- 2.(original) Coating process according to claim 1, wherein said phosphor or scintillator layer is deposited onto said flexible substrate, and wherein said substrate is continuously supplied.
- 3.(original) Coating process according to claim 1, wherein said phosphor or scintillator layer is deposited onto an area of said flexible substrate, exceeding the area of a phosphor or scintillator screen, panel or plate ready-for-use by at least 50%.
- 4.(original) Coating process according to claim 2, wherein said phosphor or scintillator layer is deposited onto an area of said flexible substrate, exceeding the area of a phosphor or scintillator screen, panel or plate ready-for-use by at least 50%.
- 5.(original) Coating process according to claim 1, wherein said phosphor or scintillator layer is deposited onto an area of said flexible substrate, exceeding the area of a phosphor or scintillator screen, panel or plate ready-for-use by at least a factor of 5.
- 6.(original) Coating process according to claim 2, wherein said phosphor or scintillator layer is deposited onto an area of said flexible substrate, exceeding the area of a phosphor or scintillator screen, panel or plate ready-for-use by at least a factor of 5.

- 7.(original) Coating process according to claim 1, wherein said phosphor or scintillator layer is deposited onto an area of said flexible substrate, exceeding the area of a phosphor or scintillator screen, panel or plate ready-for-use by at least a factor of 10.
- 8.(original) Coating process according to claim 2, wherein said phosphor or scintillator layer is deposited onto an area of said flexible substrate, exceeding the area of a phosphor or scintillator screen, panel or plate ready-for-use by at least a factor of 10.
- 9.(original) Coating process according to claim 1, wherein said substrate is, at least partially, moving over one or more roller(s) and/or guiding frame(s).
- 10.(original) Coating process according to claim 2, wherein said substrate is, at least partially, moving over one or more roller(s) and/or guiding frame(s).
- 11.(original) Coating process according to claim 3, wherein said substrate is, at least partially, moving over one or more roller(s) and/or guiding frame(s).
- 12.(original) Coating process according to claim 4, wherein said substrate is, at least partially, moving over one or more roller(s) and/or guiding frame(s).
- 13.(original) Coating process according to claim 5, wherein said substrate is, at least partially, moving over one or more roller(s) and/or guiding frame(s).
- 14.(original) Coating process according to claim 6, wherein said substrate is, at least partially, moving over one or more roller(s) and/or guiding frame(s).
- 15.(original) Coating process according to claim 7, wherein said substrate is, at least partially, moving over one or more roller(s) and/or guiding frame(s).
- 16.(original) Coating process according to claim 8, wherein said substrate is, at least partially, moving over one or more roller(s) and/or guiding frame(s).

- 17.(currently amended) Coating process according to claim 1, further comprising the step of cutting said ~~substrate~~, substrate carrying said deposited phosphor or scintillator layer.
- 18.(currently amended) Coating process according to claim 2, further comprising the step of cutting said ~~substrate~~, substrate carrying said deposited phosphor or scintillator layer.
- 19.(currently amended) Coating process according to claim 3, further comprising the step of cutting said ~~substrate~~, substrate carrying said deposited phosphor or scintillator layer.
- 20.(currently amended) Coating process according to claim 4, further comprising the step of cutting said ~~substrate~~, substrate carrying said deposited phosphor or scintillator layer.
- 21.(original) Coating process according to claim 1, wherein said substrate is moving over at least one unwinding or supplying roller and/or one roll up or winding roller, wherein none, one or both of said roller(s) is(are) present outside said sealed zone.
- 22.(original) Coating process according to claim 2, wherein said substrate is moving over at least one unwinding or supplying roller and/or one roll up or winding roller, wherein none, one or both of said roller(s) is(are) present outside said sealed zone.
- 23.(original) Coating process according to claim 3, wherein said substrate is moving over at least one unwinding or supplying roller and/or one roll up or winding roller, wherein none, one or both of said roller(s) is(are) present outside said sealed zone.
- 24.(original) Coating process according to claim 4, wherein said substrate is moving over at least one unwinding or supplying roller and/or one roll up or winding roller, wherein none, one or both of said roller(s) is(are) present outside said sealed zone.

- 25.(original) Coating process according to claim 9, wherein said substrate is moving over at least one unwinding or supplying roller and/or one roll up or winding roller, wherein none, one or both of said roller(s) is(are) present outside said sealed zone.
- 26.(original) Coating process according to claim 10, wherein said substrate is moving over at least one unwinding or supplying roller and/or one roll up or winding roller, wherein none, one or both of said roller(s) is(are) present outside said sealed zone.
- 27.(original) Coating process according to claim 11, wherein said substrate is moving over at least one unwinding or supplying roller and/or one roll up or winding roller, wherein none, one or both of said roller(s) is(are) present outside said sealed zone.
- 28.(original) Coating process according to claim 12, wherein said substrate is moving over at least one unwinding or supplying roller and/or one roll up or winding roller, wherein none, one or both of said roller(s) is(are) present outside said sealed zone.
- 29.(original) Coating process according to claim 1, wherein said flexible substrate is passing, at least once, through said coating zone by a continuous or discontinuous motion in a forward sense.
- 30.(original) Coating process according to claim 2, wherein said flexible substrate is passing, at least once, through said coating zone by a continuous or discontinuous motion in a forward sense.
- 31.(original) Coating process according to claim 3, wherein said flexible substrate is passing, at least once, through said coating zone by a continuous or discontinuous motion in a forward sense.

- 32.(original) Coating process according to claim 4, wherein said flexible substrate is passing, at least once, through said coating zone by a continuous or discontinuous motion in a forward sense.
- 33.(original) Coating process according to claim 9, wherein said flexible substrate is passing, at least once, through said coating zone by a continuous or discontinuous motion in a forward sense.
- 34.(original) Coating process according to claim 10, wherein said flexible substrate is passing, at least once, through said coating zone by a continuous or discontinuous motion in a forward sense.
- 35.(original) Coating process according to claim 11, wherein said flexible substrate is passing, at least once, through said coating zone by a continuous or discontinuous motion in a forward sense.
- 36.(original) Coating process according to claim 12, wherein said flexible substrate is passing, at least once, through said coating zone by a continuous or discontinuous motion in a forward sense.
- 37.(original) Coating process according to claim 21, wherein said flexible substrate is passing, at least once, through said coating zone by a continuous or discontinuous motion in a forward sense.
- 38.(original) Coating process according to claim 22, wherein said flexible substrate is passing, at least once, through said coating zone by a continuous or discontinuous motion in a forward sense.

- 39.(original) Coating process according to claim 23, wherein said flexible substrate is passing, at least once, through said coating zone by a continuous or discontinuous motion in a forward sense.
- 40.(original) Coating process according to claim 24, wherein said flexible substrate is passing, at least once, through said coating zone by a continuous or discontinuous motion in a forward sense.
- 41.(original) Coating process according to claim 25, wherein said flexible substrate is passing, at least once, through said coating zone by a continuous or discontinuous motion in a forward sense.
- 42.(original) Coating process according to claim 26, wherein said flexible substrate is passing, at least once, through said coating zone by a continuous or discontinuous motion in a forward sense.
- 43.(original) Coating process according to claim 26, wherein said flexible substrate is passing, at least once, through said coating zone by a continuous or discontinuous motion in a forward sense.
- 44.(original) Coating process according to claim 27, wherein said flexible substrate is passing, at least once, through said coating zone by a continuous or discontinuous motion in a forward sense.
- 45.(original) Coating process according to claim 28, wherein said flexible substrate is passing, at least once, through said coating zone by a continuous or discontinuous motion in a forward sense.

- 46.(original) Coating process according to claim 1, wherein said flexible substrate is moving in successive steps of forward and backward motion, whether or not interrupted inbetween said successive steps.
- 47.(original) Coating process according to claim 2, wherein said flexible substrate is moving in successive steps of forward and backward motion, whether or not interrupted inbetween said successive steps.
- 48.(original) Coating process according to claim 3, wherein said flexible substrate is moving in successive steps of forward and backward motion, whether or not interrupted inbetween said successive steps.
- 49.(original) Coating process according to claim 4, wherein said flexible substrate is moving in successive steps of forward and backward motion, whether or not interrupted inbetween said successive steps.
- 50.(original) Coating process according to claim 9, wherein said flexible substrate is moving in successive steps of forward and backward motion, whether or not interrupted inbetween said successive steps.
- 51.(original) Coating process according to claim 10, wherein said flexible substrate is moving in successive steps of forward and backward motion, whether or not interrupted inbetween said successive steps.
- 52.(original) Coating process according to claim 11, wherein said flexible substrate is moving in successive steps of forward and backward motion, whether or not interrupted inbetween said successive steps.

- 53.(original) Coating process according to claim 12, wherein said flexible substrate is moving
in successive steps of forward and backward motion, whether or not interrupted
inbetween said successive steps.
- 54.(original) Coating process according to claim 21, wherein said flexible substrate is moving
in successive steps of forward and backward motion, whether or not interrupted
inbetween said successive steps.
- 55.(original) Coating process according to claim 22, wherein said flexible substrate is moving
in successive steps of forward and backward motion, whether or not interrupted
inbetween said successive steps.
- 56.(original) Coating process according to claim 23, wherein said flexible substrate is moving
in successive steps of forward and backward motion, whether or not interrupted
inbetween said successive steps.
- 57.(original) Coating process according to claim 24, wherein said flexible substrate is moving
in successive steps of forward and backward motion, whether or not interrupted
inbetween said successive steps.
- 58.(original) Coating process according to claim 25, wherein said flexible substrate is moving
in successive steps of forward and backward motion, whether or not interrupted
inbetween said successive steps.
- 59.(original) Coating process according to claim 26, wherein said flexible substrate is moving
in successive steps of forward and backward motion, whether or not interrupted
inbetween said successive steps.

- 60.(original) Coating process according to claim 27, wherein said flexible substrate is moving in successive steps of forward and backward motion, whether or not interrupted inbetween said successive steps.
- 61.(original) Coating process according to claim 28, wherein said flexible substrate is moving in successive steps of forward and backward motion, whether or not interrupted inbetween said successive steps.
- 62.(original) Coating process according to claim 1, wherein said substrate is a self-supporting sheet, plate, web or panel.
- 63.(original) Coating process according to claim 2, wherein said substrate is a self-supporting sheet, plate, web or panel.
- 64.(original) Coating process according to claim 3, wherein said substrate is a self-supporting sheet, plate, web or panel.
- 65.(original) Coating process according to claim 4, wherein said substrate is a self-supporting sheet, plate, web or panel.
- 66.(original) Coating process according to claim 1, wherein said substrate is a roller web.
- 67.(original) Coating process according to claim 2, wherein said substrate is a roller web.
- 68.(original) Coating process according to claim 3, wherein said substrate is a roller web.
- 69.(original) Coating process according to claim 4, wherein said substrate is a roller web.
- 70.(original) Coating process according to claim 1, wherein said substrate is supported by a substrate holder.
- 71.(original) Coating process according to claim 2, wherein said substrate is supported by a substrate holder.

- 72.(original) Coating process according to claim 3, wherein said substrate is supported by a substrate holder.
- 73.(original) Coating process according to claim 4, wherein said substrate is supported by a substrate holder.
- 74.(original) Coating process according to claim 1, wherein said substrate is selected from the group consisting of glass, a polymeric material or a metal.
- 75.(original) Coating process according to claim 2, wherein said substrate is selected from the group consisting of glass, a polymeric material or a metal.
- 76.(original) Coating process according to claim 3, wherein said substrate is selected from the group consisting of glass, a polymeric material or a metal.
- 77.(original) Coating process according to claim 4, wherein said substrate is selected from the group consisting of glass, a polymeric material or a metal.
- 78.(original) Coating process according to claim 62, wherein said substrate is selected from the group consisting of glass, a polymeric material or a metal.
- 79.(original) Coating process according to claim 63, wherein said substrate is selected from the group consisting of glass, a polymeric material or a metal.
- 80.(original) Coating process according to claim 64, wherein said substrate is selected from the group consisting of glass, a polymeric material or a metal.
- 81.(original) Coating process according to claim 65, wherein said substrate is selected from the group consisting of glass, a polymeric material or a metal.
- 82.(original) Coating process according to claim 66, wherein said substrate is selected from the group consisting of glass, a polymeric material or a metal.

- 83.(original) Coating process according to claim 67, wherein said substrate is selected from the group consisting of glass, a polymeric material or a metal.
- 84.(original) Coating process according to claim 68, wherein said substrate is selected from the group consisting of glass, a polymeric material or a metal.
- 85.(original) Coating process according to claim 69, wherein said substrate is selected from the group consisting of glass, a polymeric material or a metal.
- 86.(original) Coating process according to claim 70, wherein said substrate is selected from the group consisting of glass, a polymeric material or a metal.
- 87.(original) Coating process according to claim 71, wherein said substrate is selected from the group consisting of glass, a polymeric material or a metal.
- 88.(original) Coating process according to claim 72, wherein said substrate is selected from the group consisting of glass, a polymeric material or a metal.
- 89.(original) Coating process according to claim 73, wherein said substrate is selected from the group consisting of glass, a polymeric material or a metal.
- 90.(original) Coating process according to claim 74, wherein said metal substrate is an aluminum layer, previously coated with a protective layer being an oxide or a polymeric compound layer, present on at least a side of said substrate moving through said vapor stream.
- 91.(original) Coating process according to claim 75, wherein said metal substrate is an aluminum layer, previously coated with a protective layer being an oxide or a polymeric compound layer, present on at least a side of said substrate moving through said vapor stream.

- 92.(original) Coating process according to claim 76, wherein said metal substrate is an aluminum layer, previously coated with a protective layer being an oxide or a polymeric compound layer, present on at least a side of said substrate moving through said vapor stream.
- 93.(original) Coating process according to claim 77, wherein said metal substrate is an aluminum layer, previously coated with a protective layer being an oxide or a polymeric compound layer, present on at least a side of said substrate moving through said vapor stream.
- 94.(original) Coating process according to claim 78, wherein said metal substrate is an aluminum layer, previously coated with a protective layer being an oxide or a polymeric compound layer, present on at least a side of said substrate moving through said vapor stream.
- 95.(original) Coating process according to claim 79, wherein said metal substrate is an aluminum layer, previously coated with a protective layer being an oxide or a polymeric compound layer, present on at least a side of said substrate moving through said vapor stream.
- 96.(original) Coating process according to claim 80, wherein said metal substrate is an aluminum layer, previously coated with a protective layer being an oxide or a polymeric compound layer, present on at least a side of said substrate moving through said vapor stream.
- 97.(original) Coating process according to claim 81, wherein said metal substrate is an aluminum layer, previously coated with a protective layer being an oxide or a polymeric

compound layer, present on at least a side of said substrate moving through said vapor stream.

98.(original) Coating process according to claim 82, wherein said metal substrate is an aluminum layer, previously coated with a protective layer being an oxide or a polymeric compound layer, present on at least a side of said substrate moving through said vapor stream.

99.(original) Coating process according to claim 83, wherein said metal substrate is an aluminum layer, previously coated with a protective layer being an oxide or a polymeric compound layer, present on at least a side of said substrate moving through said vapor stream.

100.(original) Coating process according to claim 84, wherein said metal substrate is an aluminum layer, previously coated with a protective layer being an oxide or a polymeric compound layer, present on at least a side of said substrate moving through said vapor stream.

101.(original) Coating process according to claim 85, wherein said metal substrate is an aluminum layer, previously coated with a protective layer being an oxide or a polymeric compound layer, present on at least a side of said substrate moving through said vapor stream.

102.(original) Coating process according to claim 86, wherein said metal substrate is an aluminum layer, previously coated with a protective layer being an oxide or a polymeric compound layer, present on at least a side of said substrate moving through said vapor stream.

- 103.(original) Coating process according to claim 87, wherein said metal substrate is an aluminum layer, previously coated with a protective layer being an oxide or a polymeric compound layer, present on at least a side of said substrate moving through said vapor stream.
- 104.(original) Coating process according to claim 88, wherein said metal substrate is an aluminum layer, previously coated with a protective layer being an oxide or a polymeric compound layer, present on at least a side of said substrate moving through said vapor stream.
- 105.(original) Coating process according to claim 89, wherein said metal substrate is an aluminum layer, previously coated with a protective layer being an oxide or a polymeric compound layer, present on at least a side of said substrate moving through said vapor stream.
- 106.(original) Coating process according to claim 90, wherein said metal substrate is an anodized aluminum layer having a thickness of less than 600 μm .
- 107.(original) Coating process according to claim 91, wherein said metal substrate is an anodized aluminum layer having a thickness of less than 600 μm .
- 108.(original) Coating process according to claim 92, wherein said metal substrate is an anodized aluminum layer having a thickness of less than 600 μm .
- 109.(original) Coating process according to claim 93, wherein said metal substrate is an anodized aluminum layer having a thickness of less than 600 μm .
- 110.(original) Coating process according to claim 94, wherein said metal substrate is an anodized aluminum layer having a thickness of less than 600 μm .

- 111.(original) Coating process according to claim 95, wherein said metal substrate is an anodized aluminum layer having a thickness of less than 600 μm .
- 112.(original) Coating process according to claim 96, wherein said metal substrate is an anodized aluminum layer having a thickness of less than 600 μm .
- 113.(original) Coating process according to claim 97, wherein said metal substrate is an anodized aluminum layer having a thickness of less than 600 μm .
- 114.(original) Coating process according to claim 98, wherein said metal substrate is an anodized aluminum layer having a thickness of less than 600 μm .
- 115.(original) Coating process according to claim 99, wherein said metal substrate is an anodized aluminum layer having a thickness of less than 600 μm .
- 116.(original) Coating process according to claim 100, wherein said metal substrate is an anodized aluminum layer having a thickness of less than 600 μm .
- 117.(original) Coating process according to claim 101, wherein said metal substrate is an anodized aluminum layer having a thickness of less than 600 μm .
- 118.(original) Coating process according to claim 102, wherein said metal substrate is an anodized aluminum layer having a thickness of less than 600 μm .
- 119.(original) Coating process according to claim 103, wherein said metal substrate is an anodized aluminum layer having a thickness of less than 600 μm .
- 120.(original) Coating process according to claim 104, wherein said metal substrate is an anodized aluminum layer having a thickness of less than 600 μm .
- 121.(original) Coating process according to claim 105, wherein said metal substrate is an anodized aluminum layer having a thickness of less than 600 μm .

- 122.(original) Coating process according to claim 1, wherein said step of vapor deposition is initiated by a vapor flow of raw materials from one or more container(s), and wherein said vapor flow is generated by adding energy to said raw materials and said container(s), by thermal, electric, or electromagnetic energy or a combination thereof.
- 123.(original) Coating process according to claim 2, wherein said step of vapor deposition is initiated by a vapor flow of raw materials from one or more container(s), and wherein said vapor flow is generated by adding energy to said raw materials and said container(s), by thermal, electric, or electromagnetic energy or a combination thereof.
- 124.(original) Coating process according to claim 3, wherein said step of vapor deposition is initiated by a vapor flow of raw materials from one or more container(s), and wherein said vapor flow is generated by adding energy to said raw materials and said container(s), by thermal, electric, or electromagnetic energy or a combination thereof.
- 125.(original) Coating process according to claim 4, wherein said step of vapor deposition is initiated by a vapor flow of raw materials from one or more container(s), and wherein said vapor flow is generated by adding energy to said raw materials and said container(s), by thermal, electric, or electromagnetic energy or a combination thereof.
- 126.(original) Coating process according to claim 1, wherein said step of vapor deposition proceeds by physical vapor deposition, by chemical vapor deposition or a by combination of physical and chemical vapor deposition.
- 127.(original) Coating process according to claim 2, wherein said step of vapor deposition proceeds by physical vapor deposition, by chemical vapor deposition or a by combination of physical and chemical vapor deposition.

- 128.(original) Coating process according to claim 3, wherein said step of vapor deposition proceeds by physical vapor deposition, by chemical vapor deposition or a by combination of physical and chemical vapor deposition.
- 129.(original) Coating process according to claim 4, wherein said step of vapor deposition proceeds by physical vapor deposition, by chemical vapor deposition or a by combination of physical and chemical vapor deposition.
- 130.(original) Coating process according to claim 1, wherein said phosphor or scintillator layer is a binderless layer.
- 131.(original) Coating process according to claim 2, wherein said phosphor or scintillator layer is a binderless layer.
- 132.(original) Coating process according to claim 3, wherein said phosphor or scintillator layer is a binderless layer.
- 133.(original) Coating process according to claim 4, wherein said phosphor or scintillator layer is a binderless layer.
- 134.(original) Coating process according to claim 1, wherein said phosphor is a photostimulable phosphor.
- 135.(original) Coating process according to claim 2, wherein said phosphor is a photostimulable phosphor.
- 136.(original) Coating process according to claim 3, wherein said phosphor is a photostimulable phosphor.
- 137.(original) Coating process according to claim 4, wherein said phosphor is a photostimulable phosphor.

- 138.(original) Coating process according to claim 134, wherein said photostimulable phosphor is a CsBr:Eu phosphor.
- 139.(original) Coating process according to claim 135, wherein said photostimulable phosphor is a CsBr:Eu phosphor.
- 140.(original) Coating process according to claim 136, wherein said photostimulable phosphor is a CsBr:Eu phosphor.
- 141.(original) Coating process according to claim 137, wherein said photostimulable phosphor is a CsBr:Eu phosphor.
- 142.(original) Coating process according to claim 1, wherein said phosphor is a prompt emitting luminescent phosphor.
- 143.(original) Coating process according to claim 2, wherein said phosphor is a prompt emitting luminescent phosphor.
- 144.(original) Coating process according to claim 3, wherein said phosphor is a prompt emitting luminescent phosphor.
- 145.(original) Coating process according to claim 4, wherein said phosphor is a prompt emitting luminescent phosphor.
- 146.(original) Coating process according to claim 1, further characterized by the step of applying a protective coating onto said phosphor or scintillator layer.
- 147.(original) Coating process according to claim 2, further characterized by the step of applying a protective coating onto said phosphor or scintillator layer.
- 148.(original) Coating process according to claim 3, further characterized by the step of applying a protective coating onto said phosphor or scintillator layer.

- 149.(original) Coating process according to claim 4, further characterized by the step of applying a protective coating onto said phosphor or scintillator layer.
- 150.(original) Coating process according to claim 146, wherein said protective layer is coated or laminated onto said phosphor or scintillator layer inside said sealed zone, maintained under vacuum conditions.
- 151.(original) Coating process according to claim 147, wherein said protective layer is coated or laminated onto said phosphor or scintillator layer inside said sealed zone, maintained under vacuum conditions.
- 152.(original) Coating process according to claim 148, wherein said protective layer is coated or laminated onto said phosphor or scintillator layer inside said sealed zone, maintained under vacuum conditions.
- 153.(original) Coating process according to claim 149, wherein said protective layer is coated or laminated onto said phosphor or scintillator layer inside said sealed zone, maintained under vacuum conditions.
- 154.(original) Coating process according to claim 146, wherein said protective coating or laminate is an organic resin layer.
- 155.(original) Coating process according to claim 147, wherein said protective coating or laminate is an organic resin layer.
- 156.(original) Coating process according to claim 148, wherein said protective coating or laminate is an organic resin layer.
- 157.(original) Coating process according to claim 149, wherein said protective coating or laminate is an organic resin layer.

- 158.(original) Coating process according to claim 150, wherein said protective coating or laminate is an organic resin layer.
- 159.(original) Coating process according to claim 151, wherein said protective coating or laminate is an organic resin layer.
- 160.(original) Coating process according to claim 152, wherein said protective coating or laminate is an organic resin layer.
- 161.(original) Coating process according to claim 153, wherein said protective coating or laminate is an organic resin layer.
- 162.(original) Coating process according to claim 146, wherein said protective coating or laminate is an inorganic layer.
- 163.(original) Coating process according to claim 147, wherein said protective coating or laminate is an inorganic layer.
- 164.(original) Coating process according to claim 148, wherein said protective coating or laminate is an inorganic layer.
- 165.(original) Coating process according to claim 149, wherein said protective coating or laminate is an inorganic layer.
- 166.(original) Coating process according to claim 150, wherein said protective coating or laminate is an inorganic layer.
- 167.(original) Coating process according to claim 151, wherein said protective coating or laminate is an inorganic layer.
- 168.(original) Coating process according to claim 152, wherein said protective coating or laminate is an inorganic layer.

- 169.(original) Coating process according to claim 153, wherein said protective coating or laminate is an inorganic layer.
- 170.(original) Coating process according to claim 1, further characterized by the step of laminating said substrate carrying the phosphor or scintillator layer onto a carrier layer.
- 171.(original) Coating process according to claim 2, further characterized by the step of laminating said substrate carrying the phosphor or scintillator layer onto a carrier layer.
- 172.(original) Coating process according to claim 3, further characterized by the step of laminating said substrate carrying the phosphor or scintillator layer onto a carrier layer.
- 173.(original) Coating process according to claim 4, further characterized by the step of laminating said substrate carrying the phosphor or scintillator layer onto a carrier layer.
- 174.(original) Coating process according to claim 146, further characterized by the step of laminating said substrate carrying the phosphor or scintillator layer onto a carrier layer.
- 175.(original) Coating process according to claim 147, further characterized by the step of laminating said substrate carrying the phosphor or scintillator layer onto a carrier layer.
- 176.(original) Coating process according to claim 148, further characterized by the step of laminating said substrate carrying the phosphor or scintillator layer onto a carrier layer.
- 177.(original) Coating process according to claim 149, further characterized by the step of laminating said substrate carrying the phosphor or scintillator layer onto a carrier layer.
- 178.(original) Coating process according to claim 150, further characterized by the step of laminating said substrate carrying the phosphor or scintillator layer onto a carrier layer.
- 179.(original) Coating process according to claim 151, further characterized by the step of laminating said substrate carrying the phosphor or scintillator layer onto a carrier layer.

- 180.(original) Coating process according to claim 152, further characterized by the step of laminating said substrate carrying the phosphor or scintillator layer onto a carrier layer.
- 181.(original) Coating process according to claim 153, further characterized by the step of laminating said substrate carrying the phosphor or scintillator layer onto a carrier layer.
- 182.(original) Coating process according to claim 154, further characterized by the step of laminating said substrate carrying the phosphor or scintillator layer onto a carrier layer.
- 183.(original) Coating process according to claim 155, further characterized by the step of laminating said substrate carrying the phosphor or scintillator layer onto a carrier layer.
- 184.(original) Coating process according to claim 156, further characterized by the step of laminating said substrate carrying the phosphor or scintillator layer onto a carrier layer.
- 185.(original) Coating process according to claim 157, further characterized by the step of laminating said substrate carrying the phosphor or scintillator layer onto a carrier layer.
- 186.(original) Coating process according to claim 158, further characterized by the step of laminating said substrate carrying the phosphor or scintillator layer onto a carrier layer.
- 187.(original) Coating process according to claim 159, further characterized by the step of laminating said substrate carrying the phosphor or scintillator layer onto a carrier layer.
- 188.(original) Coating process according to claim 160, further characterized by the step of laminating said substrate carrying the phosphor or scintillator layer onto a carrier layer.
- 189.(original) Coating process according to claim 161, further characterized by the step of laminating said substrate carrying the phosphor or scintillator layer onto a carrier layer.
- 190.(original) Coating process according to claim 162, further characterized by the step of laminating said substrate carrying the phosphor or scintillator layer onto a carrier layer.

- 191.(original) Coating process according to claim 163, further characterized by the step of laminating said substrate carrying the phosphor or scintillator layer onto a carrier layer.
- 192.(original) Coating process according to claim 164, further characterized by the step of laminating said substrate carrying the phosphor or scintillator layer onto a carrier layer.
- 193.(original) Coating process according to claim 165, further characterized by the step of laminating said substrate carrying the phosphor or scintillator layer onto a carrier layer.
- 194.(original) Coating process according to claim 166, further characterized by the step of laminating said substrate carrying the phosphor or scintillator layer onto a carrier layer.
- 195.(original) Coating process according to claim 167, further characterized by the step of laminating said substrate carrying the phosphor or scintillator layer onto a carrier layer.
- 196.(original) Coating process according to claim 168, further characterized by the step of laminating said substrate carrying the phosphor or scintillator layer onto a carrier layer.
- 197.(original) Coating process according to claim 169, further characterized by the step of laminating said substrate carrying the phosphor or scintillator layer onto a carrier layer.
- 198.(original) Coating process according to claim 174, wherein said step of laminating said substrate carrying the phosphor or scintillator layer is performed inside said sealed zone, maintained under vacuum conditions.
- 199.(original) Coating process according to claim 175, wherein said step of laminating said substrate carrying the phosphor or scintillator layer is performed inside said sealed zone, maintained under vacuum conditions.

- 200.(original) Coating process according to claim 176, wherein said step of laminating said substrate carrying the phosphor or scintillator layer is performed inside said sealed zone, maintained under vacuum conditions.
- 201.(original) Coating process according to claim 177, wherein said step of laminating said substrate carrying the phosphor or scintillator layer is performed inside said sealed zone, maintained under vacuum conditions.
- 202.(original) Coating process according to claim 174, wherein said carrier layer is a flexible or rigid polymer layer.
- 203.(original) Coating process according to claim 175, wherein said carrier layer is a flexible or rigid polymer layer.
- 204.(original) Coating process according to claim 176, wherein said carrier layer is a flexible or rigid polymer layer.
- 205.(original) Coating process according to claim 177, wherein said carrier layer is a flexible or rigid polymer layer.
- 206.(original) Coating process according to claim 198, wherein said carrier layer is a flexible or rigid polymer layer.
- 207.(original) Coating process according to claim 199, wherein said carrier layer is a flexible or rigid polymer layer.
- 208.(original) Coating process according to claim 200, wherein said carrier layer is a flexible or rigid polymer layer.
- 209.(original) Coating process according to claim 201, wherein said carrier layer is a flexible or rigid polymer layer.

- 210.(original) Coating process according to claim 174, wherein said carrier layer is a metal sheet.
- 211.(original) Coating process according to claim 175, wherein said carrier layer is a metal sheet.
- 212.(original) Coating process according to claim 176, wherein said carrier layer is a metal sheet.
- 213.(original) Coating process according to claim 177, wherein said carrier layer is a metal sheet.
- 214.(original) Coating process according to claim 198, wherein said carrier layer is a metal sheet.
- 215.(original) Coating process according to claim 199, wherein said carrier layer is a metal sheet.
- 216.(original) Coating process according to claim 200, wherein said carrier layer is a metal sheet.
- 217.(original) Coating process according to claim 201, wherein said carrier layer is a metal sheet.
- 218.(original) Coating process according to claim 174, wherein said carrier layer is a rigid metal sheet.
- 219.(original) Coating process according to claim 175, wherein said carrier layer is a rigid metal sheet.
- 220.(original) Coating process according to claim 176, wherein said carrier layer is a rigid metal sheet.

- 221.(original) Coating process according to claim 177, wherein said carrier layer is a rigid metal sheet.
- 222.(original) Coating process according to claim 198, wherein said carrier layer is a rigid metal sheet.
- 223.(original) Coating process according to claim 199, wherein said carrier layer is a rigid metal sheet.
- 224.(original) Coating process according to claim 200, wherein said carrier layer is a rigid metal sheet.
- 225.(original) Coating process according to claim 201, wherein said carrier layer is a rigid metal sheet.
- 226.(new) A method for coating a phosphor or a scintillator layer onto a flexible substrate, within a sealed zone maintained under vacuum conditions, by the step of vapor deposition, wherein said phosphor or scintillator layer is deposited at a coating thickness onto said substrate at a coating thickness of at least 65 μm to no more than 1000 μm , characterized in that said substrate is deformed at least before, during or after said step of vapor deposition.
- 227.(new) The method for coating a phosphor or a scintillator of claim 226 wherein said coating thickness is no more than 725 μm .
- 228.(new) The method for coating a phosphor or a scintillator of claim 226 wherein said coating thickness is no more than 500 μm .